- **8**. The device of claim **1**, wherein the semiconductor layer comprises n-type TiO₂.
- 9. The device of claim 1, wherein the electrode layer comprises gold.
- 10. The device of claim 1, further comprising an electrical connection between the nanostructured metal layer and the electrode.
 - 11. A photovoltaic device comprising:
 - a nanostructured metal layer that can absorb at least a portion of the electromagnetic spectrum of sunlight and produce hot electrons that have an energy no less than about 0.7 eV;
 - a semiconductor layer in contact with the nanostructured metal layer to form a Schottky barrier with a barrier height of about 0.7 eV;
 - an electrode layer in contact with the semiconductor layer to form an ohmic contact.
- 12. The device of claim 11, wherein the nanostructured metal layer comprises silver.
- 13. The device of claim 12, wherein the semiconductor layer comprises n-type TiO₂.
- 14. The device of claim 13, wherein the electrode layer comprises gold.
- 15. The device of claim 11, further comprising an electrical connection between the nanostructured metal layer and the electrode.

- **16**. An electronic device, comprising: a nanostructured silver layer;
- an n-type TiO₂ layer in contact with the silver layer; a metal electrode in contact with the TiO₂ layer to form an ohmic contact;
- an electrical connection between the silver layer and the metal electrode.
- 17. A method of making a photovoltaic device, comprising: depositing a metal electrode layer onto a substrate; forming a semiconductor layer on the metal layer;
- forming a nanostructured layer of a metal having a surface plasmon resonance within the visible and near-visible spectrum range on the semiconductor layer;
- wherein the nanostructured metal layer and the semiconductor layer form an interface that is a Schottky barrier; and
- wherein the electrode layer forms an ohmic contact to the semiconductor layer.
- 18. The method of claim 17, wherein the nanostructured metal layer comprises silver.
- 19. The method of claim 18, wherein the semiconductor layer comprises n-type ${\rm TiO}_2$.
- 20. The method of claim 17, wherein the electrode layer comprises gold.
- 21. The method of claim 19, wherein the nanostructured silver layer is formed by bombarding a silver target with an ultrafast laser pulse to deposit a thin film of silver nanoparticles onto the layer of TiO_2 .

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